AMAT Centura RP EPI

SERIAL NUMBER	402728
VINTAGE	2002
MAKER	AMAT
MODEL	Centura RP EPI
PROCESS	EPI
WAFER SIZE	300MM

Platform Type	300mm Centura
System Config	Application Level 1 : Reduced Pressure
	Application Level 2 : Reduced Pressure
	First in Fab System or Apps : No
	Ch-A : (RH3) Reduced PRESSURE EPI
	Ch-B : (RH3) Reduced PRESSURE EPI
	Ch-C : Empty
	Ch-D : Empty
Electrical	SEMI
Ch. A	
Thickness Control Option	AccuSETT 2
Recipe Control AccuSETT	Yes
Lamp Type	Ushio BNA8
Ch. B	
Thickness Control Option	AccuSETT 2
Recipe Control AccuSETT	Yes
Lamp Type	Ushio BNA8
Gas Delivery	

Pump Purge	**Yes**
Regulator and Displays	**Transducers and Regulators**
Transducer Display Type	**SI (KPA)**
H2 Leak Detector	**SINGLE**

Gas Pallet

	Ch. A	**Ch. B**
Slot 1	N2	N2
Slot 2	HCL	HCL
Slot 3	SiH4	SiH4
Slot 5	Si2H6	D-DOP#1
Slot 6	HCL	D-DOP#2
Slot 7	DCS	DCS
Slot 8	GeH4	GeH4
Slot 9	M-DOP#1	M-DOP#1
Slot 10	M-DOP#2	M-DOP#2

Mainframe

Mainframe Type	**STD CENTURA**
Loadlocks	**BATCH LOAD LOCK**
Upper Frame H2 Leak Detector	**Present**
Mass Flow Verification	**YES**
Multi Water Clean	**NO MVC FOR 4 CHAMBER SYSTEM**
Wafer Transfer Robot	**YASUKAWA**
ORIENTER	**PRE ALIGNER**
End effecter	**Edge grip PEEK material**
Wafer storage	**2 Slot**
Wafer Mapping	**LED sensor Detection**
Number of Load Parts	**Two**